LORENTZ SOLUTION

Press Release

Lorentz Solution's PeakView Supports TSMC RF Reference Design Kit 3.0

The PeakView EM platform provides high-frequency CMP-Enabled synthesis, simulation, extraction and modeling in the new TSMC RF RDK

SANTA CLARA, Calif. — June 1, 2011 — Lorentz Solution, Inc., the world's leading provider of Electromagnetic (EM) Design Platform Solutions for RF and High Speed Integrated Circuit Designs, today announced that PeakView® EM solution for Chemical and Mechanical Polishing (CMP) has been included in TSMC's 65 nanometer RF Reference Design Kit RDK 3.0. The PeakView CMP-Enabled EM solution provides device synthesis, simulation, extraction and modeling to the RDK for RF and AMS designs that demand the highest performance like the RDK's 60 GHz reference design completed in TSMC's 65nm design infrastructure.

PeakView CMP is supported by the critical components of EM solver, simulation modeling and device parameterization -- all in a tightly integrated design platform as part of the foundry PDK platform. With PeakView's CMP capability in the passive device modeling flow, all aspects of device performance can now be accurately analyzed for the effects of metal fill and slotting / striping patterns. CMP parameters can be customized across processes and extended as needed to deliver DRC / LVS clean designs. PeakView CMP is critical part for nanometer designs dramatically improving silicon predictability.

"The addition of Lorentz' latest EM solution to the RDK reinforces TSMC's commitment to providing the best-in-class design ecosystem for our customers," said Suk Lee, director of Design Infrastructure Marketing at TSMC. "Partnering with Lorentz enables us to continue to deliver cutting-edge RF design capability to our mutual customers for next generation wireless designs."

"A key part of PeakView's capability in the RDK is our unique EM methods for handling the CMP aspects of designs at these advanced geometries," said Jinsong Zhao, President and Founder of Lorentz Solution. "As fabrication geometries have shrunk, we are bringing new advanced capabilities designers need to deliver the highest quality parts to their customers."

TSMC has expanded its use of the PeakView EM Design Platform for nanometer RF IP development and has used PeakView EM Design Platform over the past years to develop RF IP for new nanometer processes while Process Design Kits (PDK) were under development. Over the years, Lorentz has participated in TSMC's EM accuracy qualification programs, iRCX qualification program, RF RDK programs, and LVS flow development to demonstrate the added value PeakView EM Design Platform brings to the TSMC's design ecosystem.

About Lorentz Solution, Inc

Lorentz Solution, Inc is the industry leader in supplying electromagnetic (EM) design capabilities to RF, high-speed analog and high-speed digital design community. PeakView™ EM Design Platform, Lorentz's flagship product, is widely adopted

by top IDM, fabless companies and semiconductor foundries. Based in Santa Clara, California, USA with initial funding from US-based VC firms, Lorentz Solution is continuing its multi-year profitable growth.

For more information, please contact:

Les Spruiell
Lorentz Solution, Inc.

2880 Lakeside Drive, Suite 130
Santa Clara, CA 95054

408-922-0765

www.lorentzsolution.com